

LISTING OF THE CLAIMS:

This listing of claims will replace all prior versions, and listings, of claims in the application:

1. (Currently Amended) An apparatus for forming an ultra-thin film of a semiconductor device comprising:
- a reactive chamber ~~consisting of an upper container and a lower container junctioned by an O-ring~~ having a ceiling;
 - a susceptor installed inside the reactive chamber for supporting a target substrate on which an ultra-thin film is to be formed;
 - at least two gas supply pipes for supplying at least two material gases into the reactive chamber to form an ultra-thin film on the substrate;
 - at least two gas supply controllers respectively installed at the gas supply pipes to ~~repeatedly~~ supply the material gases alternately into the chamber;
 - a gas outlet for discharging the gas from the chamber;
 - at least two remote plasma generators installed outside the reactive chamber and respectively connected to the gas supply pipes for activating the material gases supplied through the gas supply pipes; and
 - a temperature controller for controlling the temperature inside the chamber in a heat exchange method, the temperature controller being installed to surround the chamber, wherein one of the gas supply pipes surrounds another of the gas supply pipes, the gas supply pipes being arranged to penetrate the ceiling of the reactive chamber through a common inlet so as to extend to a position above the susceptor.
2. (Original) The apparatus of claim 1 further comprising:
- a grounding unit connected both to the upper container and to the lower container of the reactive chamber to clean inside of the chamber; and
 - an RF power generator connected to the susceptor to apply an RF power to the susceptor.

3. (Original) The apparatus of claim 1, wherein a position controller for moving vertically the susceptor is additionally provided in the susceptor.

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4. (Original) The apparatus of claim 1, wherein a vacuum pump is connected to the gas outlet.

5 - 11. (Withdrawn)

